

**INFORMATION DISCLOSURE STATEMENT**


Applicant : Sherman  
App. No : 10/692,243  
Filed : October 22, 2003  
For : SEQUENTIAL CHEMICAL VAPOR  
DEPOSITION  
Examiner : David P. Turocy  
Art Unit : 1762

**CERTIFICATE OF EFS WEB  
TRANSMISSION**

I hereby certify that this correspondence, and any other attachment noted on the automated Acknowledgement Receipt, is being transmitted from within the Pacific Time zone to the Commissioner for Patents via the EFS Web server on:

June 22, 2007

(Date)

  
Zi Y. Wong, Reg. No. 59410

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 3 references to be considered by the Examiner. Also enclosed are 3 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

This Information Disclosure Statement is being filed after the mailing date of a final action or after the mailing date of a Notice of Allowance. This Statement is accompanied by the fee set forth in 37 C.F.R. § 1.17(p). The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

**CERTIFICATION UNDER 37 C.F.R. § 1.97(e)(2)**

I hereby certify that no item of information contained in this Statement was cited in a communication from a foreign Patent Office in a counterpart foreign application, and, to my knowledge after making reasonable inquiry, was known to any individual designated in 37 C.F.R.

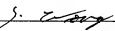
**Appl. No.** : 10/692,243  
**Filed** : October 22, 2003

**Docket No.** ASMMC.9CP1DV1D  
**Customer No.** 20,995

§ 1.56(c) more than 3 months prior to the filing of this Information Disclosure Statement.

Respectfully submitted,  
KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 6/22/07

By:   
Zi Y. Wong  
Registration No. 58,410  
Attorney of Record  
Customer No. 20,995  
(415) 954-4114

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<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>	Application No.	10/692,243	
	Filing Date	October 22, 2003	
	First Named Inventor	Sherman	
	Art Unit	1762	
(Multiple sheets used when necessary)		Examiner	David P. Turocy
SHEET 1 OF 1		Attorney Docket No.	ASMMC.9CP1DV1D

## U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number Number - Kind Code (if known) Example: 1,234,567 B1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear
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## FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T <sup>1</sup>
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## NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>1</sup>
		20a-ZC-1, MIYAMOTO et al., "High-Fluidity Deposition of SiN by Cryogenic Remote Plasma CVD," Research Center for Integrated Systems and Faculty of Engineering, Hiroshima University, 1 page	✓
		20a-ZC-2, GOTOU et al., "Atomic-Layer Deposition of SiN by Remote Plasma CVD," Research Center for Integrated Systems, Hiroshima University, 2 pages	✓
		20a-ZC-3, NAKAMURA et al., "Atomic-Layer Deposition of SiO <sub>2</sub> by Remote Plasma CVD," Research Center for Integrated Systems, Hiroshima University, 1 page	✓

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Examiner Signature	Date Considered
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\***Examiner:** Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

T<sup>1</sup> - Place a check mark in this area when an English language Translation is attached.